

Controlling MoS₂ Nanosheet Size and Network Conductivity through Alkylammonium Ion Selection

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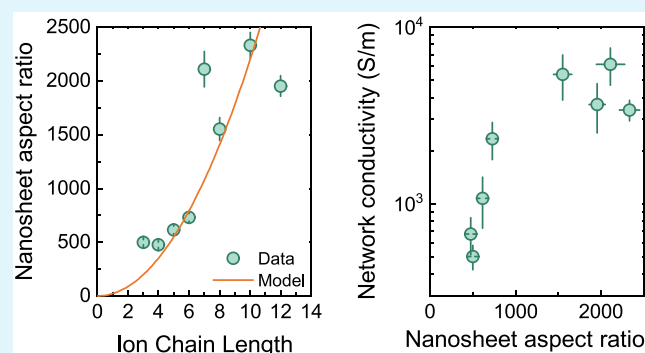
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ABSTRACT: Solution-processed inks of two-dimensional (2D) semiconductors, such as molybdenum disulfide (MoS₂), hold great promise for enabling low-cost, printed electronic devices. To optimize critical performance metrics like network conductivity, large-aspect-ratio ($k_{NS} \gg 100$) nanosheets are essential to yield low-resistance flake-to-flake junctions. While electrochemical exfoliation with ammonium salts has emerged as a viable method for producing high-aspect ratio semiconducting nanosheets, the process parameters remain underexplored. In this work, we systematically investigate the role of alkylammonium ion size in the electrochemical exfoliation of MoS₂, demonstrating control over nanosheet lengths ($L \sim 1\text{--}3 \mu\text{m}$) and nanosheet thicknesses ($t_{NS} \sim 1\text{--}4 \text{ nm}$), leading to k_{NS} values between 400 and 2500. The nanosheet aspect ratio is closely linked to ion size via the energetics of exfoliation. We fabricate networks from these nanosheets and characterize their electrical properties, revealing that higher-aspect-ratio nanosheets yield significantly more conductive networks, achieving conductivities up to 6000 Sm^{-1} . Our electrical measurements show that the network conductivity is consistent with a simple model and is limited by internanosheet junctions whose resistance scales inversely with nanosheet area. These findings suggest that ion size determines nanosheet dimensions, which in turn determine network conductivity.

KEYWORDS: solution processing, nanosheets, electrochemical exfoliation, conductivity, intercalation



INTRODUCTION

Two-dimensional (2D) semiconductors have clearly demonstrated their utility as active materials for printed electronics. Networks of solution-processed semiconductors have seen applications in transistors,¹ circuits,² sensing,³ photodetectors,⁴ photovoltaics,⁵ and thermoelectric devices.⁶ Semiconducting inks of 2D nanosheets can be mass-manufactured using liquid-phase exfoliation (LPE⁷) protocols such as shear mixing. These inks can be deposited as thin films using a range of processes, including spray coating.⁸ Such liquid-deposited films consist of networks of nanosheets and can have various morphologies depending on both nanosheet properties and deposition method.^{9,10}

However, despite the superlative properties of individual nanosheets of 2D semiconductors, efforts to replicate these properties in networks of nanosheets have been limited by the high resistance associated with nanosheet-to-nanosheet junctions.¹¹ The electrical resistance across a network can be modeled as a series of nanosheet (R_{NS}) and junction (R_J) resistances, resulting in a simple model relating network conductivity to R_{NS} and R_J (see below).¹¹ This model shows that it is essential to achieve $R_J < R_{NS}$ to maximize network

conductivity and mobility.^{11–13} The electrical resistance at these junctions may be minimized by improving the alignment of nanosheets in the network and by encouraging the formation of conformal junctions between nanosheets.^{9,11} Deploying techniques such as liquid–liquid interfacial self-assembly deposition has been shown to facilitate nanosheet alignment and conformality and so minimize R_J .^{10,14} Recently, it was predicted that nanosheets must have aspect ratios (k_{NS} , i.e., the ratio of lateral size to thickness) above a critical value to achieve conformal and aligned junctions between the nanosheets.^{12,9} Thus, to optimize the performance of printed networks, in addition to appropriate deposition methods, protocols to control the aspect ratio of the nanosheets will be required.

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61 Electrochemical exfoliation (EE) with ammonium salts is
 62 now a well-established route for obtaining large-area (high
 63 aspect ratio) semiconducting nanosheets that retain their
 64 semiconducting phase.^{15,16} EE involves driving ions between
 65 the layers of a bulk 2D crystal with a constant voltage, leading
 66 to expansion of the crystal, which facilitates subsequent
 67 exfoliation. The expanded material is then sonicated to
 68 exfoliate and disperse the material in a solvent before size
 69 selection by centrifugation. While there is now a significant
 70 amount of literature on the EE of 2D semiconductors, often
 71 focusing on a final device, relatively few studies approach the
 72 optimization of the intercalation parameter space.^{15,16} Yang et
 73 al. have shown that increasing the voltage (>7 V) and
 74 sonication time (>2 h) can significantly decrease the layer
 75 number of EE silver chromium disulfide, AgCrS₂ nanosheets,
 76 down to a bilayer material.¹⁷ In addition, the mechanical
 77 properties of the bulk crystals have also been shown to affect
 78 the success of the EE process. Lin et al. attribute their
 79 monolayer indium(III) selenide, In₂Se₃ nanosheets (aspect
 80 ratio ~ 300), to having a lower in-plane Young's modulus (E_{in}
 81 < 80 GPa) than other typical 2D crystals such as MoS₂, MoSe₂,
 82 and WSe₂ ($E_{in} \approx 200$ GPa).¹⁸ More recently, it has been found
 83 that while some materials with low in-plane Young's modulus,
 84 such as SnSe₂ ($E_{in} = 87$ GPa), exfoliate well, others with
 85 similarly low E_{in} , such as PdSe₂ ($E_{in} = 72$ GPa), do not expand
 86 well.⁷ This implies that, as with liquid phase exfoliation,¹⁹ the
 87 out-of-plane Young's modulus is also important for achieving
 88 high AR. Indeed, Carey et al. found that high values of the
 89 ratio, E_{in}/E_{out} are critical for ensuring bulk crystal expansion
 90 during the electrochemical process and for achieving higher
 91 aspect ratio nanosheets (>1000).¹³ Despite this progress,
 92 understanding the dynamic behavior of these layered materials
 93 under external stimuli remains an active area of research.²⁰

94 The most common route to electrochemically expand MoS₂
 95 is through the intercalation of alkylammonium salts into a host
 96 crystal. In this paper, we will discuss a number of such salts, as
 97 listed in Table 1, using an abbreviation based on the length of
 98 the salt's alkyl chain (C_n, where n is the number of carbons per
 99 chain).^{14,18} Common routes include tetraheptylammonium
 100 bromide (C7),^{14,18} tetrapropylammonium bromide
 101 (C3),^{1,21–23} and tetrabutylammonium bromide (C4).²¹
 102 Other less common routes, including tetraethylammonium
 103 bromide (C2),¹⁵ tetraoctylammonium bromide,^{24,25} and
 104 tetradecylammonium bromide (C10),¹⁵ have also been
 105 demonstrated. These salts were selected to form a systematic
 106 series of alkylammonium ions (C3–C12), enabling a direct
 107 investigation of how alkyl chain length affects nanosheet
 108 properties. The ions from C2 to C10 were selected based on
 109 literature precedence and commercial availability, with C12
 110 selected to extend the series. Tetraheptylammonium bromide
 111 (C7) in the solvent acetonitrile is often preferred due to the
 112 quality of the nanosheets produced, with mean nanosheet
 113 lengths (L_{NS}) between 0.5 and 2 μ m and mean nanosheet
 114 thicknesses (t_{NS}) between 2 and 5 nm,^{14,15} while smaller ions
 115 like tetrapropylammonium (C3) and tetrabutylammonium
 116 bromide (C4) in the solvent propylene carbonate enable
 117 rapid expansion but typically yield lower-aspect-ratio nano-
 118 sheets.²⁶

119 We emphasize that ion selection is fundamentally linked to
 120 solvent choice. For example, polar solvents such as propylene
 121 carbonate dissolve shorter-chain ions (C3–C6) effectively,
 122 whereas larger hydrophobic ions (C7 and larger) require less
 123 polar solvents such as acetonitrile to dissolve the salt and

Table 1. Quaternary Ammonium Ions^a

full Name	abbreviation	alkyl chain length	total carbons in ion (4 × n)
tetraethylammonium bromide	TEAB	C2	8
tetrapropylammonium bromide	TPAB	C3	12
tetrabutylammonium bromide	TBAB	C4	16
tetrapentylammonium bromide	TPentAB	C5	20
tetrahexylammonium bromide	THxAB	C6	24
tetraheptylammonium bromide	THepAB	C7	28
tetraoctylammonium bromide	TOAB	C8	32
tetradecylammonium bromide	TDAB	C10	40
tetradodecylammonium bromide	TDoAB	C12	48

^aA Range of Quaternary Ammonium Ions with their Respective Alkyl Chain Lengths and Total Number of Carbons, with C12 being the Largest and C2 the Smallest. Ions are denoted as "C_n" where n indicates the number of carbon atoms in each alkyl chain. Each quaternary ammonium ion has four identical alkyl chains, giving a total number of carbons in each ion = (4 × n).

successfully expand the crystal.¹⁶ More complex solvent effects
 also exist. For example, propylene carbonate has been shown
 to have its own intercalation effect, enabling milder
 exfoliation.²¹ Nevertheless, there may still be scope for
 optimizing solvent choice for nanosheet yields and quality.

Previous studies have established that ion size influences the
 expansion of intercalated crystals in EE, with larger ions
 generally leading to greater interlayer spacing, as measured by
 techniques like X-ray diffraction (XRD),¹⁵ or at a local level by
 scanning electron microscope (SEM).¹⁶ However, these
 techniques provide an incomplete picture. XRD offers a bulk
 average of interlayer spacing but does not give information
 about the lateral size or thickness of nanosheets, and SEM
 analysis cannot provide good statistical data on the exfoliated
 product.

Critically, the field lacks a systematic and quantitative link
 between intercalant ion size and the statistical dimensions
 (< L_{NS} >, < t_{NS} >, or the mean nanosheet aspect ratio, < k_{NS} >) of
 the exfoliated nanosheets. It remains an open question whether
 crystal expansion directly translates to larger, thinner, and
 higher-quality nanosheets in solution. Furthermore, while ion
 size has been explored from the perspective of intercalation
 efficiency, its downstream effects have so far been overlooked,
 particularly how this ion-driven control over nanosheet
 dimensions dictates the electrical performance of printed
 networks of nanosheets.^{18,27,28}

In this article, we close this knowledge gap by systematically
 examining the entire pathway from ion selection to the
 electrical properties of printed networks. We demonstrate that
 alkylammonium ion size is a powerful tool for precisely tuning
 the dimensions of solution-processed MoS₂ nanosheets. We
 then quantitatively link these tailored nanosheet properties to
 the electrical properties of the thin-film networks. This study
 moves beyond observation of crystal expansion and establishes
 a design rule for EE: ion selection enables tailoring of
 nanosheet dimensions for optimized electronic device perform-
 ance.

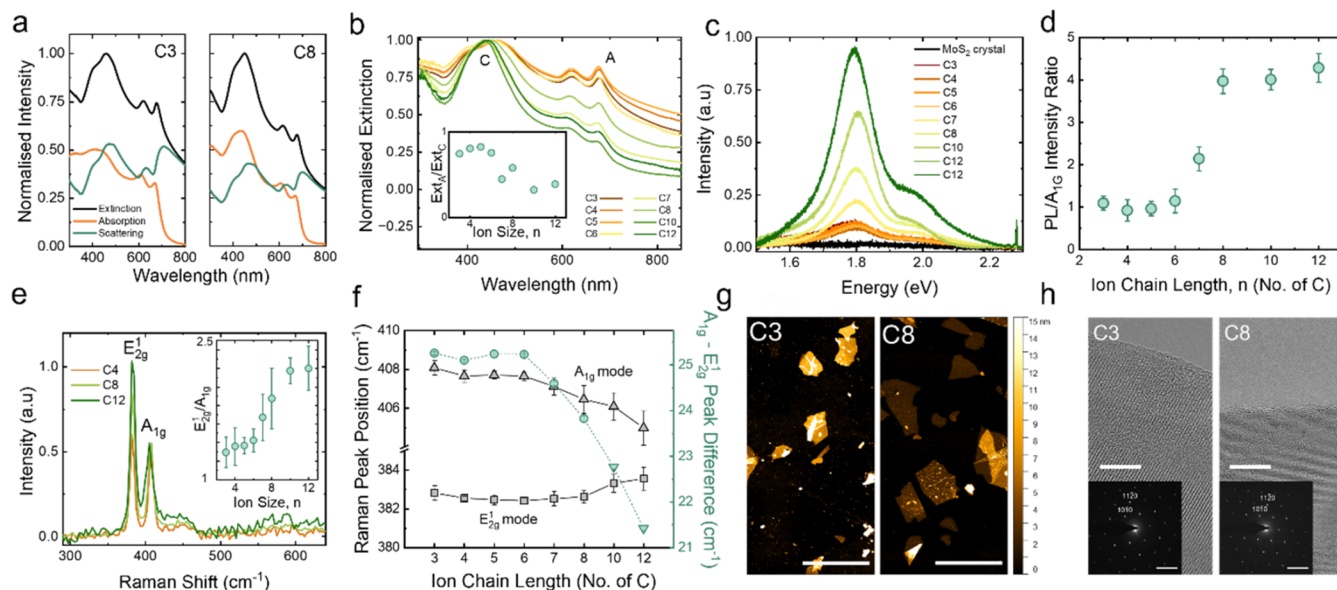


Figure 1. Nanosheet characterization. (a) UV–vis spectra of C3 and C8, respectively. (b) Overlaid extinction plots of all samples. Inset: Ratio of A-exciton peak to C-exciton peak extinction. (c) Representative PL and Raman spectra of C3–C12 inks along with the raw MoS₂ crystal. The spectra were normalized to the A_{1g} Raman mode of MoS₂ at ~406 cm⁻¹. (d) Ratio of PL peak to Raman A_{1g} mode. (e) Raman spectra for C4, C8, and C12 ions, normalized to the A_{1g} Raman mode. Inset: Ratio of E_{2g}¹ to A_{1g} scaling with *n*. (f) Positions of Raman peaks plotted with ion chain length, *n*. The difference in peak positions for each *n* is shown in green. (g) AFM images of C3 and C8 material, respectively. Each with 5 μm scale bars. (h) TEM images and inset Fourier Transforms of C3 and C8 edges, respectively. Scale bars of 10 nm in each.

161 ■ RESULTS AND DISCUSSION

162 Material Quality

163 MoS₂ was electrochemically expanded by ion intercalation into
 164 bulk crystals before exfoliation (Methods). Intercalation was
 165 performed using eight different quaternary ammonium ions,
 166 C3, C4, C5, C6, C7, C8, C10, and C12 (Table 1). Preliminary
 167 experiments revealed that no single solvent system worked
 168 effectively for all ions, requiring tailored approaches for
 169 different size ranges. For the smaller ions (C3–C6), we
 170 found propylene carbonate (PC) to be a good solvent, with
 171 attempts using acetonitrile (ACN) resulting in minimal crystal
 172 expansion and poor nanosheet yield. Conversely, the mid-sized
 173 ions (C7 and C8) showed the opposite behavior, performing
 174 poorly in PC but achieving effective intercalation when
 175 dissolved in ACN. The largest ions (C10 and C12) presented
 176 additional challenges, requiring a modified two-step procedure:
 177 we first preintercalated the crystals using C7 in ACN to
 178 partially expand the lattice, then treated them with the target
 179 larger ion also in ACN to complete the exfoliation process.¹⁷
 180 To reflect the use of this preintercalation method for these two
 181 ions, these data points are depicted with different symbols in
 182 this work. C2 was also explored but did not yield stable, usable
 183 dispersions under the conditions used for other ions and was
 184 therefore excluded from the systematic study.

185 After intercalation, the electrolyte was drained off, and the
 186 separated intercalated material was added to a PVP-DMF
 187 solution before brief ultrasonication for 5 min to complete
 188 exfoliation. The PVP is required to facilitate stabilization of the
 189 nanosheet dispersion.¹ The exfoliated material was then
 190 centrifuged at low speed, removing bulk material, and then
 191 solvent cleaning steps were carried out to remove DMF, PVP,
 192 and any nanodots. The final material was resuspended in IPA.
 193 These inks are colloidal stable in IPA, typically for up to 2
 194 weeks, and stable in DMF for up to one month. No significant
 195 changes in nanosheet dimensions were observed in this period.

It should be noted that the electrical properties of networks
 made from aged (>2 weeks) inks will not be comparable to
 those made from fresh inks, while optical properties can
 degrade even faster than this, depending on storage.²⁹
 Therefore, all samples are measured as quickly as possible
 and at the same stage of aging.

Figure 1a shows the UV–visible optical absorption spectra
 of C3 and C8 inks, obtained using an integrating sphere to
 separate the extinction and absorption of the inks, from which
 scattering can then be isolated.³⁰ Complete spectra for all
 samples can be seen in Figure S1. For all spectra, the expected
 strong excitonic transitions at 679 nm (A-exciton), 623 nm (B-
 exciton), and 440–460 nm (C-exciton) are seen. A drop in the
 intensity of the A excitonic peak relative to the C excitonic
 peak (at approximately 450 nm) in the extinction spectrum is
 an indicator of reduced thickness of the nanomaterial.^{31,32}
 Figure 1b depicts the extinction spectra for each sample with
 the intensity ratio of the A/C excitonic peaks shown in the
 inset. The A/C-exciton ratio is greatest for the smaller ion
 chain samples (C3–C6) but decreases for the C7 to C12 inks.
 It is known that small A/C ratios are consistent with thinner
 nanosheets,¹⁹ indicating that larger ions yield thinner flakes.
 The underlying cause of this behavior is that thinning the
 nanosheet increases quantum confinement and reduces
 dielectric screening. Then the higher-energy C-exciton
 (derived from deeper valence bands) is suppressed more
 strongly than the A-exciton, causing the A/C intensity ratio to
 decrease in the thinner layers. Figure 1c depicts the
 representative PL/Raman spectra of C3–C12 inks, and a
 clearly higher PL/Raman intensity ratio can be observed for
 the larger intercalating ions, suggesting a higher monolayer
 content in C8–C12 inks.^{33,34} This is also supported by the
 averaged PL/E_{2g}¹ intensity ratio in Figure 1d, where the value
 of C8–C12 is 3–4 times that of C3–C6. The raw crystal
 exhibits no appreciable photoluminescence, as expected. Taken

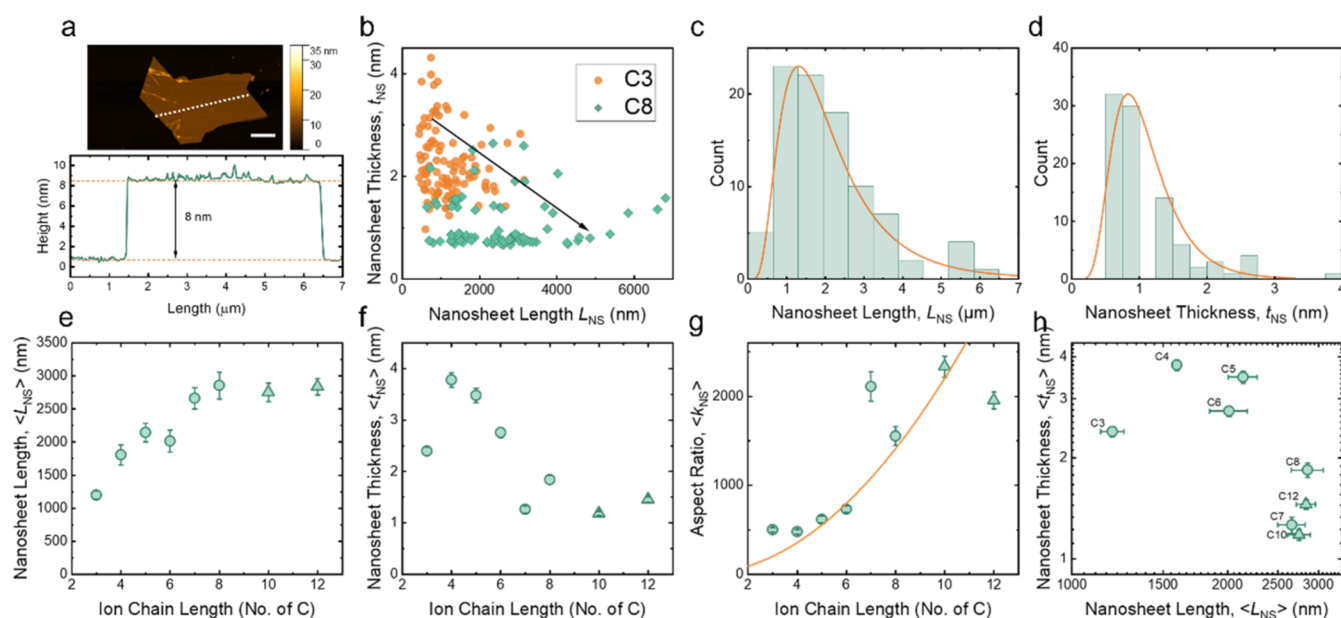


Figure 2. Size characteristics of exfoliated samples. (a) Top: AFM image of the nanosheet exfoliated using C10 with a 10 μm scale bar. Bottom: Linear profile showing measurement of length and thickness of the nanosheet. (b) The length and thickness sizing of C3 and C8 nanosheets. Arrow indicating increasing L_{NS} and reducing t_{NS} with larger ion chain sizes (c) Histogram of counts for the nanosheet length of the C8 sample with overlaid log-normal fit. (d) Histogram of counts for nanosheet thickness for the C8 sample with overlaid log-normal fit. (e–g) Mean nanosheet length, $\langle L_{\text{NS}} \rangle$, mean nanosheet thickness, $\langle t_{\text{NS}} \rangle$, and calculated mean aspect ratio, $\langle k_{\text{NS}} \rangle$, as a function of ion chain length, n , respectively. (h) Mean nanosheet thickness as a function of mean nanosheet length. The dashed line in g illustrates n^2 dependence.

231 together, these data are a strong indicator that increasing ion
232 size yields thinner nanosheets.

233 The absence of J2 and J3 vibrational modes in the Raman
234 spectra, which are attributed to the metallic 1T phase, in
235 Figure 1e provides further confirmation of the presence of the
236 semiconducting 2H phase.^{35,36} Figure S2 summarizes the
237 Raman peak positions of both the E_{2g}^1 and A_{1g} modes of all
238 inks. Interestingly, the E_{2g}^1/A_{1g} intensity ratio increases with
239 ion size (Figure 1e inset). According to our spectroscopic data
240 (confirmed below via AFM), this implies that the E_{2g}^1/A_{1g}
241 intensity ratio increases with decreasing nanosheet thickness.
242 However, for mechanically exfoliated MoS_2 , the E_{2g}^1/A_{1g}
243 intensity ratio decreases with decreasing nanosheet thickness.³⁷

244 This contradiction may be from multiple sources. It may
245 indicate the higher density of basal defects created during the
246 exfoliation process using larger intercalating ions.³⁸ Similar
247 behavior has also been observed in graphite exfoliation assisted
248 by CO_2 .³⁹ Alternatively, it may be because the presence of
249 exfoliation debris (residual solvent, polymer, etc.) results in a
250 dielectric environment that is different for liquid- versus
251 mechanically exfoliated nanosheets, leading to subtle changes
252 in Raman peak intensities. In Figure 1f, the blue shift
253 (vibration stiffening) of the E_{2g}^1 mode and red shift (vibration
254 softening) of the A_{1g} mode can be observed, which indicates
255 more complete exfoliation and decreasing average thickness
256 with increasing ion size.^{37,40} Comparing this to spectra from
257 the literature of unexfoliated MoS_2 crystal with much greater
258 peak spacing ($\approx 27 \text{ cm}^{-1}$) or our own measurement of ≈ 26
259 cm^{-1} (Figure S2) further demonstrates strong exfoliation of
260 the crystal.⁴¹

261 The exfoliated material was examined using AFM to verify
262 successful exfoliation of nanosheets, as shown in Figure 1g.
263 The images show the production of larger lateral size and
264 reduced thickness material for C8 compared to C3. TEM was
265 performed on nanosheets to assess the morphology and

266 crystalline quality of MoS_2 nanosheets following the EE
267 process (Figure 1h). Through high-angle annular dark-field
268 scanning transmission electron microscopy (HAADF-STEM)
269 imaging, the nanosheets in C3 and C8 had lateral sizes on the
270 order of micrometers with mostly smooth basal surfaces
271 (Figure S3). From relative differences in the HAADF-STEM
272 image brightness, we observed that the C8 nanosheets were
273 thinner than those of C3, despite both exhibiting large lateral
274 sizes. Distinct hexagonal spots visible in the selected area
275 electron diffraction patterns provided confirmation of single-
276 crystalline 2H phase MoS_2 nanosheets with edges primarily
277 cleaved along the zigzag direction. Despite the high aspect
278 ratios seen in C8, there is minimal wrinkling and folding of the
279 nanosheet with sharp, clear edges compared with that of C3.
280 The clean and crystalline edges visible in the HRTEM images
281 demonstrated retention of the high crystalline quality of the
282 nanosheets with minimal damage to the edges due to the
283 gentle exfoliation process (5 min sonication).

Nanosheet Size Statistics

284
285 While the spectroscopic data imply that the nanosheets get
286 thinner as ion size is increased, extensive AFM statistics are
287 required to provide definitive proof and to verify nanosheet
288 size control by alkylammonium ion choice. AFM was used to
289 generate micrographs of nanosheets, as shown in Figure 2a.
290 For each nanosheet, linear profiles along the long axes were
291 used to extract dimensions: the lateral size (L_{NS}) was taken as
292 the profile length, while the apparent thickness was determined
293 by averaging the height measurements from each profile. This
294 apparent thickness was then converted to layer number using
295 previously reported step height analysis⁴² and then converted
296 to real nanosheet thickness, t_{NS} , by multiplying the layer
297 number by the crystallographic thickness of MoS_2 (0.615
298 nm ⁴³). Profiles were measured and analyzed for around 100
299 nanosheets in each sample. Figure 2b shows a scatter plot of

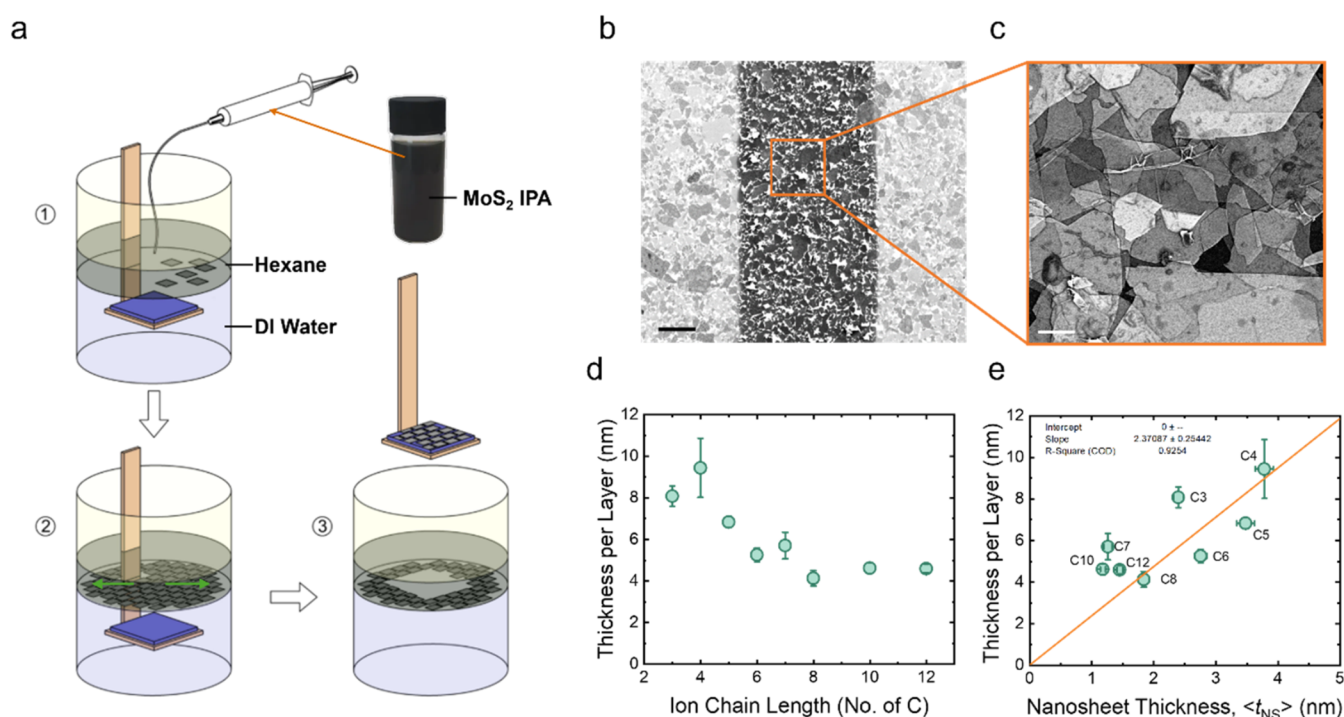


Figure 3. Deposition and characterization of thin MoS₂ films. (a) Schematic of the deposition of thin films. Step 1 is the deposition of MoS₂ nanosheets in the water-hexane interface. Step 2 shows the spread and alignment of nanosheets parallel to the interface, causing the compression of nanosheets against the edges of the container, as indicated by the green arrows. Step 3 is the liftoff of the substrate through the interface, depositing the closed film on the substrate. (b) Low-resolution SEM image showing edge-to-edge aligned C8 nanosheets across gold contacts with single-layer deposition. Scale bar 20 μm . (c) Higher resolution SEM image of a single-layer MoS₂ film. Scale bar 10 μm . (d) Thickness per layer of films plotted versus ion chain length. (e) The network thickness per layer as a function of thickness (t_{NS}) of deposited nanosheets. This indicates that each layer is approximately two nanosheets thick.

300 L_{NS} vs t_{NS} for C3 and C8, with the arrow showing increasing
 301 L_{NS} and decreasing t_{NS} with increasing ion size. We note that
 302 the thinnest nanosheets observed are approximately 0.6 nm
 303 thick, consistent with clean monolayers. Example histograms
 304 showing L_{NS} and t_{NS} for C8 are shown in Figure 2c and d,
 305 respectively. These follow a log-normal distribution typical of
 306 size statistics for similar material.¹⁹

307 From histograms such as those in Figure 2c,d, (full
 308 histograms of L_{NS} and N shown in Figures S4 and S5,
 309 respectively) the mean nanosheet length and thickness, $\langle L_{\text{NS}} \rangle$
 310 and $\langle t_{\text{NS}} \rangle$, were calculated for each sample. This data are
 311 plotted versus ion chain length, n , in Figure 2e,f. The
 312 nanosheet length is seen to increase with intercalating size,
 313 from the C3 ion's $\langle L_{\text{NS}} \rangle = 1198 \pm 62$ nm to the C12 ion's
 314 $\langle L_{\text{NS}} \rangle = 2838 \pm 123$ nm. Additionally, the nanosheet thickness
 315 was the largest for C4 with $\langle t_{\text{NS}} \rangle = 3.8 \pm 0.1$ nm, and the
 316 smallest for C10 with $\langle t_{\text{NS}} \rangle = 1.2 \pm 0.1$ nm. This leads to a
 317 trend of increasing mean aspect ratio (k_{NS}) with the size of the
 318 intercalating ion, with aspect ratio increasing from $\langle k_{\text{NS}} \rangle =$
 319 500 ± 24 for C3 to $\langle k_{\text{NS}} \rangle = 2333 \pm 120$ for C10. This
 320 demonstrates that increasing the size of the intercalating ion
 321 used yields larger, thinner nanosheets in electrochemical
 322 exfoliation (Figure 2h), in line with the spectroscopic results.

323 We can begin to understand the dependence of nanosheet
 324 dimensions on ion size as follows. We have previously shown
 325 that, for nanosheets produced by liquid exfoliation, in the ideal
 326 case the aspect ratio is given by $k_{\text{NS}} \propto E_{\text{IP}}/E_{\text{OOP}}$, where E_{IP} is
 327 the energy required (per unit area) to tear a nanosheet and
 328 E_{OOP} is the energy required (per unit area) to separate two
 329 nanosheets stacked on top of each other by van der Waals

interactions.¹⁹ The van der Waals energy of attraction between 330
 two nanosheets scales with their separation, D , as $V_{\text{vdW}} \propto -1/$ 331
 D^4 .⁴⁴ N.B. the exponent differs from the interatomic value of 6 332
 due to the effect of adding large numbers of pairwise 333
 interatomic interactions.⁴⁵ Ion intercalation results in the 334
 increase in intermonolayer separation from the normal value to 335
 a value which we can approximate by the ion size, d . Here, the 336
 ion size is determined by the number of carbons in the side 337
 groups, n . Due to bond rotations, these groups will follow a 338
 roughly random walk geometry, allowing us to approximate: d 339
 $\propto n^{1/2}$.⁴⁶ Then the energy to separate to infinity two sheets
 340 initially separated by a distance d is $E_{\text{OOP}} = V_{\text{vdW}}(D = \infty) -$ 341
 $V_{\text{vdW}}(D = d)$. This means $E_{\text{OOP}} \propto 1/d^4$. We note that we expect 342
 E_{IP} to be independent of n . Combining these results yields k_{NS} 343
 $\propto n^2$. We have superimposed this n^2 behavior on Figure 2g, 344
 finding reasonable agreement with the experimental data, 345
 although the scatter inherent to AFM measurements means 346
 alternative functions cannot be ruled out. Nonetheless, the 347
 consistency with the theoretically derived n^2 dependence 348
 suggests that ion intercalation significantly weakens intersheet 349
 binding, leading to higher aspect ratio flakes after exfoliation. 350

Film Deposition and Morphological Characterization 351

352 These nanosheets typically find applications in areas such as
 353 printed electronics in the form of printed thin films of
 354 nanosheets.² It is therefore necessary to fabricate such films
 355 and assess their electrical performance. To achieve conformal
 356 networks of these nanosheets and to minimize wastage of ink,
 357 we have used a liquid-liquid interface deposition technique to
 358 deposit nanosheets on substrates for electronic testing.^{14,47} As
 359 illustrated in Figure 3a, when nanosheets are deposited at the

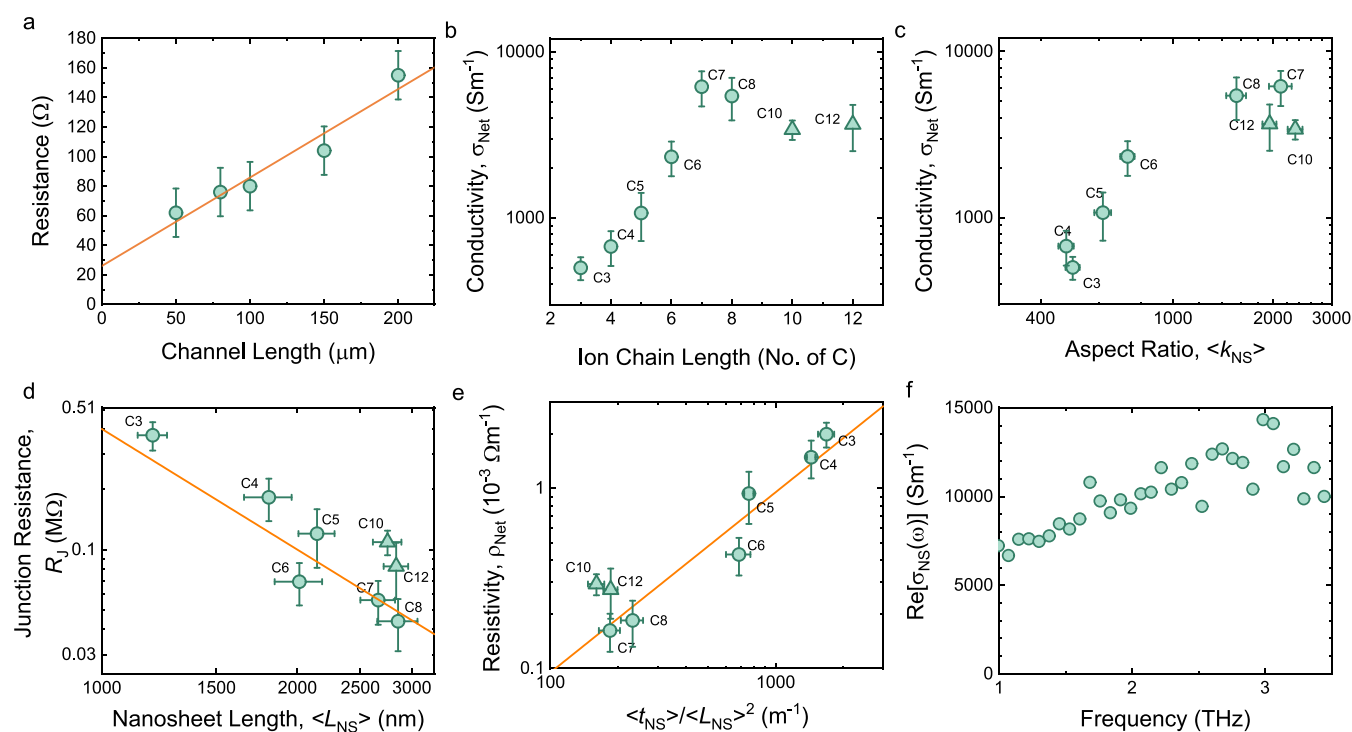


Figure 4. Electrical characterization of thin films. (a) Transmission Line Method plot to extract contact resistance and conductivity of measured samples. (b) Conductivity of film as a function of ion chain length. (c) Conductivity as a function of mean aspect ratio. (d) Calculated Junction Resistance (R_j) as a function of mean nanosheet length. (e) Conductivity as a function of t_{NS}/L^2 . (f) Terahertz Time-Domain Spectroscopy showing optical conductivity plotted versus frequency.

360 interface of water and hexane, the interfacial tension between
 361 the two liquids causes nanosheets to align, yielding a highly
 362 conformal network.^{14,47} SEM images of a single-layer film
 363 (Figure 3b, c) reveal a high degree of in-plane alignment of the
 364 nanosheets. All imaging was performed on a single-layer
 365 deposition for clarity. All electrical measurements were
 366 conducted on 3-layer films. This was to ensure networks
 367 were at least 10 nm thick to ensure sufficient network
 368 connectivity and to avoid percolation effects, which would
 369 dominate the conductivity of networks <5 nm thick.¹⁴

370 In order to facilitate electrical characterization, bottom
 371 contacts (100 nm gold with a 2 nm Ti bonding layer) were
 372 deposited on glass. Interdigitated electrodes (IDEs) with a
 373 width of 19 nm and channel lengths varying between 40 and
 374 250 μm were used to enable contact resistance correction.⁴⁸ In
 375 all cases, three complete nanosheet layers were deposited to
 376 create a fully connected nanosheet network,^{14,48} followed by
 377 annealing at 120 $^\circ\text{C}$ for 1h in an inert N_2 environment. Film
 378 thicknesses were measured by using White Light Interferom-
 379 etry (WLI), with the network thicknesses per layer shown in
 380 Figure 3d. The film thickness per layer is plotted versus the
 381 nanosheet thickness (measured by AFM) in Figure 3e. This
 382 shows that each layer is approximately two nanosheets thick on
 383 average.

384 Electrical Characterization

385 Finally, devices made from each ink were characterized using a
 386 probe station in an inert environment to reduce variations in
 387 device properties. In ambient conditions, film conductivities
 388 can fluctuate rapidly from changes in humidity,⁴⁹ light,⁵⁰ and
 389 atmospheric gases.⁵¹ The in-plane resistance for each sample
 390 was measured as a function of the channel length. From this,
 391 the contact resistance was extracted using the Transmission

Line Method (TLM),⁵² with an example for C7 shown in 392
 Figure 4a. The network conductivity, σ_{Net} for each film was 393
 calculated and plotted versus the ion size in Figure 4b. We note 394
 that on this graph, we have differentiated between samples 395
 (C3–C8), which were prepared using a one-step intercalation 396
 process, from those made using a two-step intercalation 397
 process (C10–C12). This graph shows that σ_{Net} increases with 398
 increasing ion size, reaching a maximum at C7, after which it 399
 falls off slightly. 400

It is likely that the apparent dependence of network 401
 conductivity on ion size is a reflection of the change in 402
 nanosheet dimensions with ion size observed in Figure 2. For 403
 example, a strong scaling of conductivity with aspect ratio is 404
 observed in Figure 4c, indicating that the nanosheet size has a 405
 crucial impact on the electrical properties of the nanosheet 406
 network. This scaling appears to apply between C3 and C8, 407
 while C10 and C12 show lower conductivity than expected 408
 given their aspect ratio. This indicates that although nanosheet 409
 dimensions play a pivotal role in dictating electrical conduction 410
 through nanosheet networks, the nature of the intercalation 411
 procedure (one-step versus two-step) also plays a role. 412

In order to understand the factors limiting conductivity in 413
 these networks, we apply a recently published network 414
 conduction model.¹¹ This model can be simplified to represent 415
 networks of nanosheets with moderate to high carrier density, 416
 such that the network conductivity is given by 417

$$\sigma_{\text{Net}} = \frac{(1 - P_{\text{Net}})}{\rho_{\text{NS}} + 2t_{\text{NS}}R_j} \quad (1) \quad 418$$

where P_{Net} is the network porosity, ρ_{NS} is the nanosheet 419
 resistivity, t_{NS} is the mean nanosheet thickness, and R_j is the 420
 junction resistance (for neatness, we neglect the $\langle \rangle$ symbols 421

indicating means in the equations in this paper). We note that this model has been shown to accurately describe the electrical properties of networks of graphene, WS₂, and WSe₂ nanosheets with low aspect ratio produced by liquid phase exfoliation,¹¹ networks of high aspect ratio graphene and MoS₂ nanosheets produced by electrochemical exfoliation,⁹ as well as networks of silver nanowires^{11,53} and nanoplatelets.¹¹

In almost all cases, networks are limited by transport across internanosheet junctions such that the nanosheet resistance is much smaller than the junction resistance. Under these circumstances, $\rho_{\text{NS}} < 2t_{\text{NS}}R_{\text{J}}$, allowing us to rewrite eq 1: $R_{\text{J}} \approx (1 - P_{\text{Net}})/2t_{\text{NS}}\sigma_{\text{Net}}$. Then, using the measured values of t_{NS} and an estimated value of $P_{\text{Net}} = 10\%$ (reasonable for networks of electrochemically exfoliated nanosheets), we convert our network conductivity values to approximate junction resistance values, with R_{J} plotted versus mean nanosheet length ($\langle L_{\text{NS}} \rangle$) in Figure 4d. We find a clear trend of reducing R_{J} with increasing $\langle L_{\text{NS}} \rangle$ for the one-step samples (C3–C8), with the two-step samples (C10–C12) lying slightly above the trendline.

It is known that higher aspect ratio nanosheets tend to bend and conform to one another, creating highly aligned contacts between nanosheets at the internanosheet junctions.⁹ It is likely that larger nanosheets achieve greater overlap when stacked, giving a junction area that scales with nanosheet area, i.e., $A_{\text{J}} = fL_{\text{NS}}^2$, where f is a constant which is ~ 0.25 .⁹ We propose that the junction resistance scales with junction area as $R_{\text{J}} = (RA)_{\text{J}}/A_{\text{J}} = (RA)_{\text{J}}/fL_{\text{NS}}^2$ where $(RA)_{\text{J}}$ is a constant that quantifies internanosheet sheet charge transfer. This equation is consistent with the behavior seen in Figure 4e. Fitting the C3–C8 data using this model finds very good agreement with $(RA)_{\text{J}}/f = 4 \pm 0.4 \times 10^{11} \Omega\text{m}^2$. Estimating $f = 0.25$ gives $(RA)_{\text{J}} = 1.0 \pm 0.1 \times 10^{11} \Omega\text{m}^2$. This compares to recently estimated values of $1.3 \pm 0.1 \times 10^{11} \Omega\text{m}^2$, and $1.6 \pm 0.1 \times 10^{11} \Omega\text{m}^2$ for electrochemically exfoliated MoS₂ networks.^{11,54} We note that the fact that all of the C3–C8 data points lie close to the fit line implies that all of these networks have very similar values of $(RA)_{\text{J}}/f$. This in turn implies that neither exposure to the ions during intercalation nor the presence of residual adsorbed ions in the network results in modifications in junction resistance that scale with ion size. Furthermore, because $(RA)_{\text{J}}$ has been observed to scale with the ρ_{NS} ,¹¹ this suggests no significant ion size-dependent impact on ρ_{NS} .

We can use this relationship between junction resistance and nanosheet size to rewrite eq 1 in terms of the network resistivity and nanosheet dimensions

$$\rho_{\text{Net}} \approx \frac{1}{(1 - P_{\text{Net}})} \left[\rho_{\text{NS}} + \frac{2(RA)_{\text{J}}t_{\text{NS}}}{fL_{\text{NS}}^2} \right] \quad (2)$$

This implies that the nanosheet resistivity scales linearly with $\langle t_{\text{NS}} \rangle / \langle L_{\text{NS}} \rangle^2$. As shown in Figure 4e, we find this to be approximately the case, excluding the C10 and C12 samples. However, we find that the scatter is such that we cannot accurately identify the intercept and so cannot quantify the nanosheet resistivity.

As indicated above, the electrical resistivity is higher for ions larger than C8. This is at least partly because of the higher junction resistances, as indicated in Figure 4d, but may also be due to increased nanosheet resistivity. PL/Raman analysis indicates that larger ions and the preintercalation step are impacting material quality as seen by changes in the PL/Raman spectra described in Figure 1c and d, which are

attributed to defects generated in the basal plane. These changes in material quality impact the electronic properties of the nanosheet networks, reducing the network conductivity for C8 and particularly for C10 and C12.

Terahertz time-domain spectroscopy (THz-TDS) was performed to extract nanosheet electronic data parameters for a film of C8 nanosheets. Measurements were taken in various positions on the film, yielding similar results. A representative spectrum is shown in Figure 4f. This data show relatively low frequency dispersion with THz conductivity values between 7,000 and 14,000 S/m. Averaging over multiple films yields a mean THz conductivity of 10800 ± 1500 S/m. Assuming this is a reasonable proxy for the DC conductivity of the nanosheets themselves allows us to estimate $\rho_{\text{NS}} \sim 10^{-4} \Omega\text{m}$. This value is consistent with nanosheet mobilities of ~ 60 cm²/(V s) and carrier densities of $\sim 10^{25}$ m⁻³, which are reasonable for EE MoS₂.^{11,14} This implies the presence of residual ions to not significantly alter the electrical properties of individual nanosheets. In addition, the closeness of this value to our lowest ρ_{Net} shows the electrical properties of our best networks (e.g., C7, $\rho_{\text{Net}} \approx 1.7 \times 10^{-4} \Omega\text{m}$, $\sigma_{\text{Net}} \approx 6000$ S/m) are approaching those of the nanosheets themselves. We emphasize that these high-conductivity networks are facilitated by low-resistance junctions, which are in turn associated with large area, very thin nanosheets.

We believe that controlling the size of intercalated alkylammonium ions is an important tool to control the properties of printed networks and their devices. Intercalating these ions increases the interlayer spacing during intercalation via their steric volume, reducing the van der Waals attraction between adjacent monolayers and thereby facilitating complete separation during exfoliation. This enlarged spacing, together with residual surface-bound ions, also helps suppress restacking during exfoliation and ink formulation by maintaining larger effective separation distances between the nanosheets. Because junction resistance is highly sensitive to nanosheet geometry and overlap area, this ion-driven control over nanosheet length and thickness acts as a form of “junction engineering”: larger, thinner nanosheets generated by larger ions form wider, more conformal contacts that reduce R_{J} , whereas smaller ions produce shorter, thicker nanosheets that lead to smaller junction areas and higher junction resistance. Thus, ion selection indirectly governs the junction resistance by dictating nanosheet dimensions and junction morphology in printed networks.

CONCLUSION

In this work, we demonstrated that the alkylammonium ion size serves as a critical parameter for controlling the size and electrical properties of electrochemically exfoliated MoS₂ nanosheets. By tailoring the intercalant ion, we achieved precise tuning of nanosheet lengths ($L_{\text{NS}} = 1\text{--}3 \mu\text{m}$) and aspect ratios ($k_{\text{NS}} = 400\text{--}2500$). Additionally, we found that networks of these dimension-controlled nanosheets demonstrate a strong dependence of network conduction on both nanosheet aspect ratio and $\langle t_{\text{NS}} \rangle / \langle L_{\text{NS}} \rangle^2$. This confirms that larger, thinner nanosheets have reduced junction resistances, in agreement with theoretical models of flake-to-flake junction resistance.

This work highlights the importance of the alkylammonium ion choice in the electrochemical exfoliation process. It also shows the importance of nanosheet dimensions in maximizing the electrical performance of nanosheet networks. Both factors

544 should serve as a guide to future work in the electrochemical
545 exfoliation of 2D materials, as well as optimizing electronic
546 conduction through networks of 2D materials in printed
547 electronics. These insights provide a roadmap for creating
548 printed electronics: for applications requiring high conductiv-
549 ity, such as gas sensors, strain gauges, and flexible electronics,
550 our results recommend using larger ions (C8–C12) to
551 produce large, thin nanosheets that minimize junction
552 resistance, a primary bottleneck in network devices. Shorter,
553 thicker nanosheets (C3–C6) will form higher porosity
554 networks with more exposed nanosheet edges, making them
555 superior candidates for applications as electrochemical sensors,
556 battery electrodes, or photocatalytic systems.

557 The strategy of ion-selected exfoliation may also be
558 transferable to other semiconducting transition metal dichal-
559 cogenides (e.g., WS₂, MoSe₂) for tailoring their nanosheet and
560 network properties. Ultimately, by linking quaternary ion
561 selection to nanosheet geometry and network performance,
562 this work provides a roadmap for designing high-performance,
563 solution-processed 2D material devices

564 ■ METHODS

565 Electrochemical Exfoliation

566 A thin piece of MoS₂ crystal was cleaved from an as-received crystal
567 (Sofer Group, UCT Prague) to be used as the cathode during
568 electrochemical exfoliation. Platinum foil (Alfa Aesar) was used as the
569 anode. Small copper crocodile clips were used to hold the electrodes
570 in place. The chosen alkylammonium ion was dissolved in 40 mL of
571 either propylene carbonate (PC) or acetonitrile (ACN) to prepare the
572 electrolyte. For smaller ions (C3–C6), a 3 g/L solution was prepared
573 in PC, while for intermediate-sized ions (C7 and C8), a 3 g/L
574 solution was prepared in ACN. A constant potential of 7 V was then
575 applied across the working and counter electrodes for 30 min to
576 intercalate the MoS₂ crystal. For the largest ions (C10 and C12), a
577 two-step intercalation process was employed: first, the MoS₂ was
578 preintercalated using 1 g/L C7 in ACN at 7 V for 20 min, followed by
579 a second intercalation step with 3 g/L of either C10 or C12 in ACN
580 under identical conditions. In all cases, the electrolyte turned yellow,
581 and the presence of Br⁻ indicated that intercalation of ions into the
582 material was occurring. The MoS₂ crystal expanded to many times its
583 original volume after 30 min, indicating successful intercalation of the
584 crystal.

585 The solvent was drained off, and the expanded material was added
586 to 30 mL of 1 g/L poly(vinylpyrrolidone) (PVP, molecular weight
587 ~40,000) in dimethylformamide (DMF). This was bath ultra-
588 sonicated for 5 min to complete exfoliation of the material. The
589 resulting dispersion was then centrifuged (Hettich Mikro 220R, 1195-
590 A, radius 87 mm) at 24 g for 30 min to remove unexfoliated material.
591 To remove the PVP, the 24 g of supernatant was redispersed in 30 mL
592 of DMF and was centrifuged at 3824 g for 60 min. This was repeated.
593 The resulting sediment was then redispersed in IPA and centrifuged at
594 3824 g for 60 min. The final sediment was then redispersed in IPA
595 again, giving the cleaned dispersion.

596 Thin Film Deposition

597 Masks with interdigitated electrodes (IDEs) were attached to 2 × 2
598 cm² glass with channel lengths of 50, 80, 100, 150, and 200 μm. 80
599 nm of gold and 10 nm of Cr as an adhesion layer were evaporated
600 onto the mask and substrate using a Temescal DC-2000 system to
601 create bottom contacts.

602 Cleaned substrates were required for the deposition of thin films.
603 Substrates were sonicated in acetone, purified water, and IPA for 10
604 min each. This removed residue or debris on the substrates, which
605 would disrupt film deposition.

606 Films were deposited using a dip coater setup, as published
607 recently.¹⁴ 40 mL of deionized (DI) water were added to a 50 mL
608 beaker. The substrate was then mounted on a dip coater, and the

substrate was then slowly (1 mm/s) lowered into the beaker of DI 609
water. 2 mL of hexane was added, creating a liquid–liquid interface. A 610
stirrer was added, and the beaker was stirred gently throughout the 611
process to ensure a uniform spread of the nanosheets across the 612
interface. The ink was loaded into a 5 mL syringe and then fitted into 613
a syringe pump. The injection rate was initially set to 60 μL/min and 614
then slowed to 20 μL/min when the film began to compress. When 615
the film had become fully compressed and homogeneous, the 616
substrate was slowly lifted from the beaker at a rate of 1 mm/s using 617
the dip coater. The film was allowed to dry at room temperature for 618
30 min, before being annealed at 40 °C for 1 h to dry fully. This 619
process was then repeated twice, giving three-layer films. The three- 620
layer films were then annealed at 120 °C in an argon environment. 621
While trace amounts of PVP and organic residue remain after 622
annealing and washing steps,⁵⁵ the consistent protocol across all 623
samples ensures any residual organic content is relatively constant. 624
Moreover, films in the bulk regime (>10 nm) have their transport 625
dominated by internanosheet junctions rather than residues on the 626
nanosheets.^{9,11} 627

Electrical Measurements. Electrical characteristics were meas- 628
ured in an argon environment by using a Keithley 2612A source 629
meter connected to a probe station. Extracted resistances were plotted 630
versus IDE channel lengths, with the TLM method used to extract 631
contact resistance from the intercept. The slopes of these plots were 632
then used to calculate the conductivity of each sample. TLM plots for 633
each sample are seen in S7 634

635 Material Characterization

Atomic Force Microscopy (AFM). A Bruker Multimode 8 636
scanning probe microscope was used in ScanAsyst mode (non- 637
contact) in air under ambient conditions using aluminum-coated 638
silicon cantilevers (OLTESPA-R3). Substrates for AFM were coated 639
with (3-Aminopropyl)triethoxysilane (APTES) by soaking them in a 640
solution of APTES and deionized water for 15 min. Substrates were 641
then removed and washed by rinsing with deionized water and 642
pressurized nitrogen repeatedly. Inks as used for films were deposited 643
on APTES-coated SiO₂ wafers (5 × 5 mm²). A single drop of the 644
dispersion (10 μL) was dropped onto the prepared substrate, held for 645
30 s, and then blown off with pressurized nitrogen. The sample was 646
then rinsed with water, followed by isopropanol, which was then 647
blown off with pressurized nitrogen. This prevents solvent airdrying 648
on the substrate, creating the coffee ring effect. This process was then 649
repeated with further drops of dense coverage of nanosheets across 650
the sample that could be seen under an optical microscope. AFM scan 651
sizes of between 15 × 15 and 30 × 30 μm² were used for shorter and 652
longer nanosheet samples, respectively. Scan rates between 0.35 and 653
0.7 Hz were used, taking either 512 or 1024 lines per image for 654
smaller or larger images, respectively. Respective images for each 655
sample can be found in S6. 656

AFM Statistics. To extract quantitative data on nanosheet sizing of 657
each sample, AFM statistics were carried out on the AFM images. 658
Linear profiles were extracted for imaged nanosheets along the longest 659
axis (the length), and from these, the thickness of the nanosheet was 660
also measured. Nanosheet thickness measurements by AFM are 661
typically offset due to the tip–sample effects as well as residues 662
around the nanosheets. We correct for these effects via step height 663
analysis using previous AFM measurements of MoS₂ step height as 1.9 664
nm.⁴² This height is generally considered to represent the measured 665
monolayer thickness with deviations from expectations due to the 666
aforementioned tip–sample and residue effects. The nanosheet's 667
apparent thickness was converted to the layer number by dividing the 668
apparent thickness by this step height. From the layer number, the 669
real thickness, *t*_{NS}, was calculated using a crystallographic thickness of 670
0.615 nm for MoS₂.⁴³ However, we note that this approach cannot 671
fully eliminate the effects of organic residues and may be expected to 672
lead to a small systematic error. To account for the disproportionate 673
contribution of larger nanosheets to network properties, the volume- 674
weighted mean layer number was calculated as 675

$$\langle N \rangle_V = \frac{\sum_i N_i \cdot V_i}{\sum_i V_i} \quad (3)$$

677 where N_i is the layer number and V_i is the volume of each nanosheet.
678 This was used to obtain the mean thickness, $\langle t_{NS} \rangle$, for each sample.
679 The mean nanosheet length ($\langle L_{NS} \rangle$) was calculated as the arithmetic
680 mean of the measured lengths.⁴²

681 **Optical Absorption Spectroscopy.** The spectra of nanosheet
682 dispersions were collected by Lambda spectrometer from 900 to 200
683 nm with a 1 nm step and 2 nm slit width. The dispersion was placed
684 in a 10 mm long optical length cuvette. The absorption spectra were
685 collected in an integrating sphere. The solvent spectra were subtracted
686 from the collected extinction and absorption spectra of nanosheet
687 dispersions to yield only nanosheet spectra for each. The scattering
688 spectra were obtained by subtracting the absorption from the
689 extinction spectra.

690 **Photoluminescence (PL) and Raman spectroscopy.** Raman and
691 PL data for MoS₂ nanosheet films were collected in a Renishaw Invia
692 system equipped with a ×50 objective. A 532 nm laser source was
693 used and the power of the laser was kept under ~1 mW to avoid
694 damage to the sample. The exposure time was 10, and 10 spectra at
695 different spots of each sample were collected for averaging the data.
696 The collection range was 534 to 800 nm (2.32 eV to 1.55 eV). All
697 PL/Raman data were fitted to a Lorentzian. The films were deposited
698 on glass via Langmuir–Schaffer deposition.

699 **Scanning Electron Microscopy.** SEM imaging was conducted
700 using a Carl Zeiss Ultra SEM. A secondary electron detector was used
701 to obtain the images at a 3 kV accelerating voltage, 5 mm working
702 distance, and 30 μm aperture.

703 **Transmission Electron Microscopy (TEM) Sample Preparation.** A
704 drop was placed on a lacey carbon copper TEM grid. The TEM grid
705 was then placed in a Coors alumina boat within a quartz glass tube
706 (27 mm inner diameter and 28 mm outer diameter) in a Thermo
707 Scientific Lindberg Blue M Mini-Mite tube furnace. The tube was
708 purged with 500 sccm of argon–hydrogen (15% H₂) gas. The flow
709 was reduced to 200 sccm, and the furnace was heated to 300 °C
710 (ramp: 15 °C/min) and held for 1 h. The furnace was cooled
711 naturally to room temperature in flowing argon–hydrogen gas before
712 removing the TEM grid.

713 **TEM Instrumentation.** Imaging was performed in a FEI Talos
714 F200X equipped with a cold field emission gun operated at 200 kV.
715 Selected area electron diffraction (SAED) was acquired using a 40 μm
716 diameter aperture. Bright-field (BF-) and off-axis dark-field (DF-)
717 TEM imaging was acquired by placing a 15 μm diameter aperture on
718 the transmitted beam (BF-TEM) or diffracted spot (DF-TEM). High-
719 angle annular dark-field scanning transmission electron microscopy
720 (HAADF-STEM) images were acquired using an annular detector
721 with a collection angle of 42–244 mrad, camera height of 115 mm,
722 and convergence angle of 30 mrad. Energy dispersive X-ray
723 spectroscopy (EDS) was acquired in STEM mode by using a
724 Super-X detector. Fast Fourier Transform (FFT) analysis was
725 performed by using DigitalMicrograph software. EDS maps were
726 analyzed and generated by using Thermo Fisher Scientific Velox
727 Software.

728 **Terahertz Time-Domain Spectroscopy (THz-TDS).** The samples
729 were half-covered during measurements such that the uncovered half
730 serves as an on-chip reference, eliminating realignment errors when
731 the optical path was switched between the sample and reference. THz
732 transmission measurements were carried out in a nitrogen atmosphere
733 inside a purge box with a THz spectrometer driven by a 90 fs pulsed
734 1.55 μm, 100 MHz Er-doped fiber laser (Menlo Systems). The laser
735 delivered an ≈20 mW average power to both the photoconductive
736 emitter and detector antennas (Menlo Systems). Time-resolved THz
737 transients from both the sample and the on-chip reference were
738 recorded. To suppress internal Fabry–Perot echoes of the 1.5 mm
739 quartz, a simple time gate was applied that removed the first
740 reflection. Fast Fourier transformation yields the complex trans-
741 mission spectrum, which was converted to sheet conductivity $\sigma(\omega)$
742 with Tinkham's thin-film equation. Volume conductivity was obtained

by dividing σ by the physical film thickness of 8.3 nm, as obtained
from atomic force microscopy at a scratch in the MoS₂ film.

■ ASSOCIATED CONTENT

Supporting Information

The Supporting Information is available free of charge at
<https://pubs.acs.org/doi/10.1021/acsami.5c24890>.

UV/vis extinction, absorption, and scattering spectra for
all samples; raman spectra for all samples; HAADF-
STEM morphological assessment; nanosheet length and
layer number histograms; representative AFM images of
each sample; and resistance as a function of channel
length for each sample (PDF)

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813 Notes

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